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**mr-Rem 700: NMP and NEP free alternative for photoresist removal**

In 2009 the European Union reclassified N-Methylpyrrolidone (NMP, CAS [872-50-4]) to a category 2 reprotoxin requiring R61 "May cause harm to unborn child". NMP is listed as a Substance of Very High Concern (SVHC). NMP is a constituent of the remover **mr-Rem 660**. Already in 2010 micro resist technology developed NMP-free alternatives - **mr-Rem 400** and **mr-Rem 500** - for the removal of photoresists.

In 2013 the European Union reclassified N-Ethyl-2-pyrrolidone (NEP, CAS [2687-91-4]) to a category 2 reprotoxin requiring R61 "May cause harm to unborn child". NEP is a constituent of the removers **mr-Rem 400** and **mr-Rem 500**. In 2014 micro resist technology has therefore developed the NMP & NEP free alternative mr-Rem 700 for the removal of photoresists.

We would like to ensure that we currently do not plan to discontinue the products **mr-Rem 660**, **mr-Rem 400** and **mr-Rem 500**, however we can already provide and recommend a safer alternative.

Product		Application Remover for photoresists
<b>mr-Rem 660</b>	NMP containing	All positive and negative photoresists
<b>mr-Rem 400</b>	NMP free NEP containing	Positive photoresists (ma-P 1200, ma-P 1275 G) and negative resists (ma-N 2400, ma-N 400, ma-N 1400)
<b>mr-Rem 500</b>	NMP free NEP containing	Strongly crosslinking negative photoresists (EpoCore, EpoClad, mr-UVL 6000, mr-EBL 6000, mr-DWL) Positive photoresists after processing with high thermal load
<b>mr-Rem 700</b>	NMP free NEP free	All positive and negative photo photoresists

The safer alternative **mr-Rem 700** exhibits high resist removal efficiency and can be used in the same manner as described for the NMP containing remover mr-Rem 660 and NEP containing removers mr-Rem 400 and mr-Rem 500.



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